

Title (en)  
PHOTOCURABLE COMPOSITION

Title (de)  
LICHTHÄRTBARE ZUSAMMENSETZUNGEN

Title (fr)  
COMPOSITION PHOTODURCISSABLE

Publication  
**EP 2841994 A1 20150304 (EN)**

Application  
**EP 13718670 A 20130401**

Priority  
• US 201213457657 A 20120427  
• US 2013034756 W 20130401

Abstract (en)  
[origin: US2013288162A1] A low surface energy photoresist composition is described that comprises a silicone-polyether block copolymer, wherein the silicone block comprises 35 wt. % or more of said copolymer. When compounded with a photoresist composition, the composition enables the release of a phototool from the photoresist layer.

IPC 8 full level  
**G03F 7/004** (2006.01); **G03F 7/027** (2006.01); **G03F 7/038** (2006.01)

CPC (source: EP US)  
**G03F 7/0046** (2013.01 - EP US); **G03F 7/027** (2013.01 - EP US); **G03F 7/038** (2013.01 - EP US)

Citation (search report)  
See references of WO 2013162829A1

Citation (examination)  
WO 2009076389 A1 20090618 - 3M INNOVATIVE PROPERTIES CO [US], et al

Designated contracting state (EPC)  
AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

Designated extension state (EPC)  
BA ME

DOCDB simple family (publication)  
**US 2013288162 A1 20131031**; **US 8715904 B2 20140506**; CN 104246610 A 20141224; CN 104246610 B 20190308; EP 2841994 A1 20150304; KR 20150006007 A 20150115; TW 2014111275 A 20140316; WO 2013162829 A1 20131031

DOCDB simple family (application)  
**US 201213457657 A 20120427**; CN 201380021735 A 20130401; EP 13718670 A 20130401; KR 20147033051 A 20130401; TW 102113349 A 20130415; US 2013034756 W 20130401